NA Microlithography Committee Meeting

San Jose Convention Center
Thursday, February 25th, 2010
6:00 PM to 8:00 PM

Agenda

1.0 Call to Order
- 1.1 Introduction
- 1.2 Anti-Trust Reminder
- 1.3 Intellectual Property Reminder
- 1.4 International Meeting Guidelines
- 1.5 Agenda Review

2.0 Review and Approval of SEMICON West Meeting Minutes

3.0 Staff & Liaison Reports
- 3.1 SEMI Staff Report
- 3.2 SEMI Japan
- 3.3 SEMI Europe

4.0 Ballot Review
- 4.1 Doc. 4781, Withdrawal of P38-1103, Specification For Absorbing Film Stacks And Multilayers On Extreme Ultraviolet Lithography Mask Blanks
- 4.2 (Blue Ballot) Doc. 4580, New Standard: EUV Reticle Reference Fiducial Marks

5.0 Task Force Reports
- 5.1 Data Path
- 5.2 EUV Mask
- 5.3 EUV Reticle Fiducial Mark
- 5.4 Mask Orders (P10)
- 5.5 Overlay Metrology Specifications
- 5.6 Terminology of Metrology
- 5.7 Scatterometry

6.0 SNARFs & TFOFs

7.0 Old Business
- 7.1 Previous Action Items
  - 7.1.1 Wes Erck and Susan Turner to continue working the Liquid Chemicals Committee for Microlithography photoresist standards due for 5-Year Review

8.0 New Business
- 8.1 P10 WG Findings Report
- 8.2 Next Meeting SEMICON West 2010
- 8.3 5-Year Review

9.0 Review
- 9.1 Action item review

10.0 Adjournment